

PATENT

Attorney Docket No.: AMAT/2890.C3/CMP/CMP/RKK

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What is claimed is:

1. A polishing article for chemical mechanical polishing, comprising:
 - a generally elongated polishing sheet having a polishing surface and formed from a material that is substantially opaque; and
 - a discrete region extending substantially the length of the polishing sheet that is at least semi-transparent.
2. The polishing article of claim 1, wherein the polishing surface includes a plurality of projecting surface features disposed across the polishing surface with a substantially uniform spacing.
3. The polishing pad of claim 2, wherein the discrete region includes projecting surface features and wherein the spacing between adjacent features is greater in the discrete region than in the polishing surface.
4. The article of claim 2, wherein the discrete region lacks the projecting surface features.
5. The article of claim 1, wherein the polishing material includes polyurethane with an additive.
6. The article of claim 1, wherein the discrete region includes polyurethane.
7. The article of claim 1, wherein the polishing sheet includes a plurality of layers.
8. The article of claim 7, wherein the polishing sheet includes an covering layer and a backing layer.
9. The article of claim 8, wherein the covering layer comprises polyurethane having cells.

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10. The article of claim 8, wherein the backing layer comprises fibers.
11. The article of claim 1, wherein the discrete region has a width of about 1 centimeter.
12. The article of claim 1, wherein the polishing sheet comprises a continuous belt.
13. The article of claim 1, wherein the polishing sheet comprises a linear sheet.
14. The article of claim 1, wherein the discrete region extends approximately down the center of the polishing sheet.
15. A polishing article for chemical mechanical polishing, comprising:
 - a generally elongated polishing sheet having a polishing surface, the polishing surface having a plurality of projecting surface features disposed across the polishing surface with a substantially uniform first spacing; and
 - a discrete region on the polishing surface in which the projecting surface features have a second spacing greater than the first spacing.
16. The article of claim 15, wherein the discrete region extends substantially the length of the polishing sheet.
17. The article of claim 15, wherein the polishing sheet comprises a continuous belt.
18. The article of claim 15, wherein the polishing sheet comprises a linear sheet.
19. A polishing article for chemical mechanical polishing, comprising:

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a generally elongated polishing sheet having a polishing surface, the polishing surface having a plurality of projecting surface features disposed across the polishing surface with a substantially uniform first spacing; and

a discrete region on the polishing surface which lacks the projecting surface features.

20. The article of claim 19, wherein the discrete region extends substantially the length of the polishing sheet.

21. The article of claim 19, wherein the polishing sheet comprises a continuous belt.

22. The article of claim 19, wherein the polishing sheet comprises a linear sheet.